



00839.000449

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

ATSUSHI KOIKE ET AL.

Application No.: 09/982,846

Filed: October 22, 2001

For: METHOD FOR FORMING  
A DEPOSITED FILM BY  
PLASMA CHEMICAL VAPOR  
DEPOSITION

Examiner: E. Kielin

Group Art Unit: 2813

October 21, 2002

Commissioner for Patents  
Washington, D.C. 20231

AMENDMENT AND RESPONSE TO RESTRICTION REQUIREMENT

Sir:

In response to the Office Action dated September 20, 2002, Applicants respectfully request entry of the following amendments and comments into the file of the above-identified application.

I hereby certify that this correspondence is being deposited with the United States Postal Service as first-class mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231 on

October 21, 2002

(Date of Deposit)

Alan P. Force

(Name of Attorney for Applicant)

*Alan P. Force*

Signature

October 21, 2002

Date of Signature

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